

<b>Notice of References Cited</b>	Application/Control No.	Applicant(s)/Patent Under Reexamination	
	09/895,910	BASAVANHALLY ET AL.	
	Examiner Hae M Hyeon	Art Unit 2839	Pag 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5,346,583 ✓	09-1994	Basavanhally, Nagesh R.	216/26
	B	US-5,394,493 ✓	02-1995	Ames, Gregory H.	385/35
	C	US-5,550,942 ✓	08-1996	Sheem, Sang K.	385/53
	D	US-5,566,262 ✓	10-1996	Yamane et al.	385/33
	E	US-6,078,714 ✓	06-2000	Cavanaugh, David Barr	385/115
	F	US-6,328,482 ✓	12-2001	Jian, Benjamin Bin	385/88
	G	US-6,396,995 ✓	05-2002	Stuelpnagel et al.	385/136
	H	US-6,478,606 ✓	11-2002	McNerney et al.	439/415
	I	US-6,587,618 ✓	07-2003	Raguin et al.	385/33
	J	US-6,595,698 ✓	07-2003	Gutierrez et al.	385/85
*	K	US-2003/0021547 A1	01-2003	Bolle, Cristian A.	385/82
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
*	N	EP 1271192 A1	01-2003	European Patent	BASAVANHALLY et al.	G02B 06/08
*	O	JP 2003029074 A	01-2003	Japan	BASAVANHALLY et al.	G02B 06/24
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.